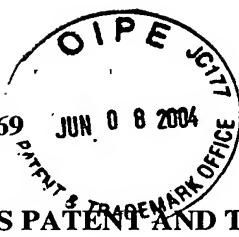


Practitioner's Docket No. 081468-0306369
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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: OTTENS et al.

Application No.: 10/743,272

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET
37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Applicant information is being added.

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